

ABSTRACT

A gas supply method includes an impurity removal step of discharging,
from a container (2) through a discharge line (5), an exhaust gas including an
5 impurity gas produced by vaporization, in the container (2), of impurities in a
solid material, and a gas supply step of supplying, from the container (2) to a
film formation chamber through a supply line (9), a supply gas including a
material gas for film formation produced by vaporization, in the container (2),
of a main component of the solid material excluding impurities. The impurity
10 removal step includes a first temperature stage of holding a temperature in the
container (2) in a first temperature range, a second temperature stage of
holding the temperature in the container (2) in a second temperature range,
and a first temperature increase stage of increasing the temperature in the
container (2) stepwise from the second to the first temperature stage.